



先导元创

腔体 Chamber



密封面粗糙度优



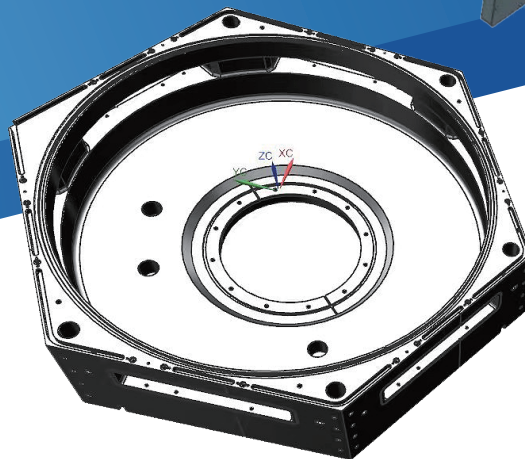
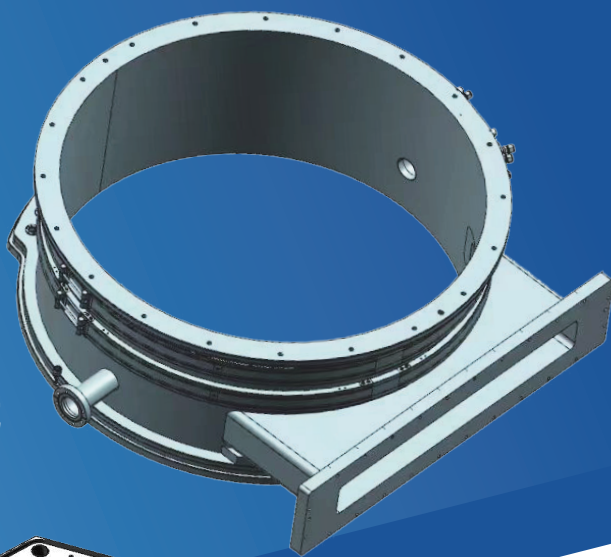
BDV优



腔体密封好



涂层性能优



密封面粗糙度

$Ra < 0.2\mu m$

膜厚均一性

$\pm 5\% \mu m$

BDV

$> 600V/mil$

漏率

$< 1E-11 \text{ torr.L/min}$

遮蔽工艺界限

$\leq \pm 0.2mm$

腔体涂层

阳极/APS/电镀镍

腔体类型

PM/TM/LL

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